Pictured is a 300 mm Silicon Dioxide Film Thickness Standard. The certified area encircled at its center, is an ample 10 mm in diameter.

The derived film thickness value is determined using a single layer model, with the refractive index of the silicon substrate chosen to match the values used by the National Institute of Standards and Technology.

PRODUCT SPECIFICATIONS

- **SEMI Specification Silicon Wafers**
  - 100, 125, 150, 200 and 300 mm diameter wafers

- **Available Silicon Dioxide Thicknesses**
  - 2, 4.5, 7.5, 12, 25, 50, 100, 200, 400, 675, and 1010 nm

- **Traceability**
  - Traceable to SI units through NIST